

## SEARCH REQUEST FORM

Scientific and Technical Information Center

Requester's Full Name: Marianne Padgett Examiner #: 65027 Date: 3/7/04  
 Art Unit: 1702 Phone Number 30-272-1425 Serial Number: 10/635,514  
 Mail Box and Bldg/Room Location: KEM 8D71 Results Format Preferred (circle): PAPER DISK E-MAIL

If more than one search is submitted, please prioritize searches in order of need.

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Please provide a detailed statement of the search topic, and describe as specifically as possible the subject matter to be searched. Include the elected species or structures, keywords, synonyms, acronyms, and registry numbers, and combine with the concept or utility of the invention. Define any terms that may have a special meaning. Give examples or relevant citations, authors, etc, if known. Please attach a copy of the cover sheet, pertinent claims, and abstract.

Title of Invention: Resist composition

Inventors (please provide full names): Kaneko et al (see attached)

Earliest Priority Filing Date: 1/31/02 for PCT patent

\*For Sequence Searches Only\* Please include all pertinent information (parent, child, divisional, or issued patent numbers) along with the appropriate serial number.

Cyclopolymerization, fluorinated diene  
and "blocked acidic groups"

see claims 1 and 2 (attached) for chemical  
formula of fluorinated diene

<b>STAFF USE ONLY</b>		Type of Search	Vendors and cost where applicable
Searcher:	<u>EZ</u>	NA Sequence (#)	STN <u>\$ 241.06</u>
Searcher Phone #:		AA Sequence (#)	Dialog
Searcher Location:		Structure (#)	<u>(5) (subset) Questel/Orbit</u>
Date Searcher Picked Up:		Bibliographic	Dr.Link
Date Completed:	<u>3-12-04</u>	Litigation	Lexis/Nexis
Searcher Prep & Review Time:	<u>5</u>	Fulltext	Sequence Systems
Clerical Prep Time:		Patent Family	WWW/Internet
Online Time:	<u>70</u>	Other	Other (specify)

=> file reg  
FILE 'REGISTRY'  
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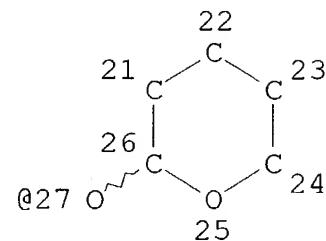
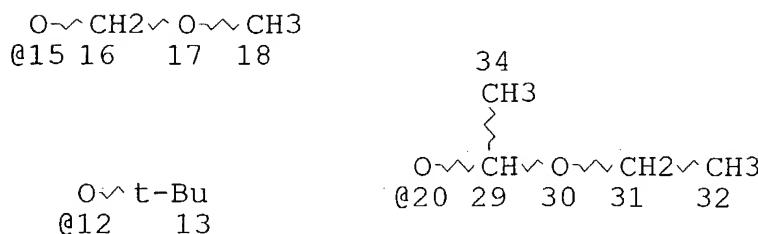
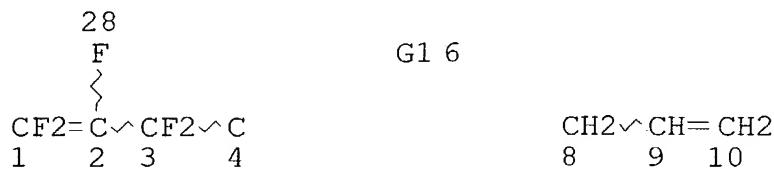
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L4 STR L2  
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L7 0 S L1 SSS SAM SUB=L6  
L8 12 S L1 SSS FUL SUB=L6  
SAV L8 PAD514A/A  
  
FILE 'CAOLD'  
L9 0 S L8  
L10 20 S L6  
  
FILE 'HCAPLUS'  
L11 7 S L8  
L12 194 S L6  
L13 159068 S RESIST OR RESISTS OR PHOTORESIST? OR MASK? OR PHOTOMASK  
L14 22 S L12 AND L13  
L15 6 S L11 AND L13  
L16 11225 S BLOCK?(2A)ACID?  
L17 4620 S ACID?(2A)LABIL?  
L18 46990 S ACTIV?(2A)(HYDROGEN# OR H)  
L19 3 S L12 AND L16  
L20 2 S L12 AND L17  
L21 0 S L12 AND L18  
  
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L22 132 S L6 AND C H F O/ELF  
L23 30 S L22 AND PMS/CI  
  
FILE 'HCAPLUS'  
L24 73 S L22

L25            25 S L23  
 L26            21 S (L24 OR L25) AND L13  
 L27            13555 S PAG OR PAGS OR PHOTOACID? OR PHOTOGENERAT? OR PHOTO(2A)  
 L28            7 S L12 AND L27  
 L29            13 S L11 OR L15 OR L19 OR L20 OR L28  
 L30            10 S (L14 OR L26) NOT L29

## FILE 'REGISTRY'

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 L1                STR



VAR G1=12/15/20/27

NODE ATTRIBUTES:

DEFAULT MLEVEL IS ATOM

DEFAULT ECLEVEL IS LIMITED

GRAPH ATTRIBUTES:

RING(S) ARE ISOLATED OR EMBEDDED

NUMBER OF NODES IS 28

STEREO ATTRIBUTES: NONE

L4                STR



NODE ATTRIBUTES:

NSPEC IS RC AT 3

DEFAULT MLEVEL IS ATOM

DEFAULT ECLEVEL IS LIMITED

GRAPH ATTRIBUTES:

RING(S) ARE ISOLATED OR EMBEDDED  
NUMBER OF NODES IS 5

STEREO ATTRIBUTES: NONE

L6 346 SEA FILE=REGISTRY SSS FUL L4  
L8 12 SEA FILE=REGISTRY SUB=L6 SSS FUL L1

100.0% PROCESSED 26 ITERATIONS

12 ANSWERS

SEARCH TIME: 00.00.01

=> file hcaplus

FILE 'HCAPLUS'

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L29 ANSWER 1 OF 13 HCAPLUS COPYRIGHT 2004 ACS on STN

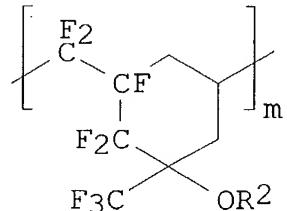
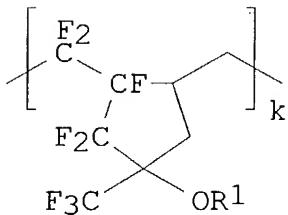
2004:37354 Document No. 140:119866 **Photoresist** materials

with excellent transparency, alkali solubility, and plasma etching resistance and pattern formation method using them. Hatakeyama, Jun; Harada, Yuji; Kawai, Yoshio (Shin-Etsu Chemical Industry Co., Ltd., Japan). Jpn. Kokai Tokkyo Koho JP 2004012886 A2 20040115, 36 pp. (Japanese). CODEN: JKXXAF. APPLICATION: JP 2002-167293 20020607.

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